

eVictor GX20 Physical Vapor Deposition System

System Overview

eVictor GX20 is a fully automated general PVD sputtering system that supports a wide variety of applications and material in a high capacity platform. It has a flexible chamber configuration around dual transfer modules and can be configured with up to ten modules.



eVictor GX20

Substrate Size:	150 mm, 200 mm
Technology Markets:	IC, Power IC, MEMS, LED and Advanced Packaging
Process Modules:	Up to 10*
Deposit material:	Cu, Ti, Ta, Al, AlSi, AlCu, Ni, NiV, Ag, Au, TiW, SiO ₂ , Mo, Si, Ir, Hf, Pt ITO, SiO ₂ , TiO ₂ , HfO ₂ , Ta ₂ O ₅ , TaO _x , TiN, TaN

*See the Polaris G620 for lower capacity requirements

Processes

- Metal films
- Oxide films
- Through silicon via deposition

Production Advantages

- Excellent temperature and particle control
- High target utilization rate and low operating costs
- Optimized software algorithms and process recipes provide higher throughput and lower cost of operation
- Dual vacuum transfer modules
- Flexible chamber configuration with up to ten process modules, including Degas, Preclean and PVD
- Manual or SMIF load lock ports